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著者	北上修
journal or	IEEE Transactions on Magnetics
publication title	
volume	41
number	10
page range	3175-3177
year	2005
URL	http://hdl.handle.net/10097/47576

doi: 10.1109/TMAG.2005.855282

# CoPtCr–SiO<sub>2</sub> Perpendicular Media for High Density Recording With a High Order Magnetic Anisotropy Energy Term

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The first and second order energy terms of uniaxial magnetic anisotropy,  $K_{u1}$  and  $K_{u2}$ , of CoPtCr–SiO<sub>2</sub> perpendicular recording media were studied as a function of film composition and film structure. Moreover, the fabrication of CoPtCr–SiO<sub>2</sub> media having adequate values of  $K_{u1}$  and  $K_{u2}$  for high recording density was preliminarily studied. An analysis of CoPtCr films with various kinds of seed layer materials revealed that the values of  $K_{u1}$  and  $K_{u2}$  varied significantly with the seed layer material used, probably due to epitaxial growth of CoPtCr on the seed layers.  $K_{u2}$  increased, accompanied by a reduction in  $K_{u1}$  as the c/a ratio of the hcp–CoPtCr lattice increased. Moreover, experimental results suggest that a high stacking-fault density enhances the  $K_{u2}$  values, especially in the high Pt content region. The addition of SiO<sub>2</sub> reduces the total anisotropy,  $K_{u1} + K_{u2}$ , but no significant change in the ratio of  $K_{u2}/K_{u1}$ was observed. The fabrication of CoPtCr–SiO<sub>2</sub> media with adequate values of  $K_{u1}$  and  $K_{u2}$  was successfully demonstrated, although more intensive efforts to enhance grain isolation are required to confirm the advantages conferred by the  $K_{u2}$  term.

Index Terms—CoPtCr–SiO<sub>2</sub>, high order energy term, lattice deformation, magnetic anisotropy, perpendicular recording media, thermal stability.

## I. INTRODUCTION

T IS theoretically predicted that the high order energy term  $\mathbf{I}$  of uniaxial magnetic anisotropy,  $K_{u2}$ , enhances the energy barrier for the remanent state, without a notable change in the switching field [1]–[4]. CoPtCr–SiO<sub>2</sub> perpendicular media deposited on Ru seed layers show negligibly small  $K_{u2}$  values, although the first order energy terms of uniaxial magnetic anisotropy,  $K_{u1}$ , of these media are exceedingly large, reaching  $1 \times 10^7$  erg/cm<sup>3</sup> [5], [6]. However, the values of  $K_{u1}$  and  $K_{u2}$  for CoPtCr media vary significantly with the seed layer materials used, probably due to epitaxial growth of CoPtCr on the seed layers, and the use of certain seed layers leads to an appearance of  $K_{u2}$  [5], [6]. In this study, the magnetic anisotropy of CoPtCr-SiO<sub>2</sub> perpendicular recording media, including the  $K_{u2}$  term is examined as a function of film composition and film structure. Moreover, the fabrication of CoPtCr–SiO 2 media with adequate values of  $K_{u1}$  and  $K_{u2}$  for high density recording is preliminarily studied.

## **II. EXPERIMENTAL PROCEDURE**

CoPtCr–SiO<sub>2</sub> media were deposited on 2.5-in glass disks by the co-sputtering method with Co, Pt, Cr, and SiO<sub>2</sub> targets using an UHV-magnetron sputtering system. The film composition was varied by controlling the deposition rates. The standard film thickness of the CoPtCr layer was 10 nm. Various kinds of materials were used as seed layers (10–20 nm in thickness), with Pt/Ta or Ta pre-seed layers underneath. The substrates were not



Fig. 1. Values of  $K_{u1}$  (open symbols) and  $K_{u2}$  (solid symbols) for  $(Co_{90}Cr_{10})_{80}Pt_{20}$  films deposited on various kinds of seed layer materials, as a function of the c/a values.

heated during the deposition process. The Ar pressure during deposition of the CoPtCr films was either 0.3 or 0.5 Pa. However, the Ar pressure during the seed layer deposition was 1.5 or 2 Pa when CoPtCr–SiO<sub>2</sub> media were fabricated. The values of  $K_{u1}$  and  $K_{u2}$  were evaluated by the GST method [7]. The recording performance was studied for double-layered media with CoZrNb (200 nm) soft under layers using a SPT flying head for the recording (track width 180 nm) and a GMR head for the read back (shield gap length 55 nm and track width 140 nm).

## **III. RESULTS AND DISCUSSION**

Fig. 1 shows the values of  $K_{u1}$  and  $K_{u2}$  for (Co<sub>90</sub> Cr <sub>10</sub>) <sub>80</sub>Pt<sub>20</sub> films without SiO<sub>2</sub> deposited on various kinds of seed layer materials, as a function of the c/a values of the hcp-CoPtCr

Digital Object Identifier 10.1109/TMAG.2005.855282



Fig. 2. Values of  $K_{u1}$  (open symbols) and  $K_{u2}$  (solid symbols) for  $(Co_{90}Cr_{10})_{75}Pt_{25}$  films deposited on various seed layer materials, as a function of the c/a values.

TABLE I RATIO OF X-RAY DIFFRACTION INTENSITY OBTAINED USING SYNCHROTRON RADIATION

Seed materials used	Ru	Pt	Pd
Normalized intensity ratio fcc(111)/hcp(101)	1	2.3	4.2
for $(Co_{90}Cr_{10})_{80}Pt_{20}$ films			
$K_{u1} (x10^6 \text{ erg/cm}^3)$	11.9	7.7	5.2
$K_{u2} (x10^6 \text{ erg/cm}^3)$	< 0.01	1.1	1.4
K <sub>u2</sub> /K <sub>u1</sub>	< 0.01	0.14	0.26

lattices. X-ray diffraction (XRD) and transmission electron microscopy (TEM) analyses revealed that all CoPtCr films had a hcp structure with the (002) plane parallel to the film plane. The c-axis distribution,  $\Delta\theta_{50}$ , of hcp-CoPtCr grains ranges from 3 to 8°, depending on the seed layer materials used, however the difference in  $\Delta\theta_{50}$  values due to the seed layer materials was negligible for the following discussion. The CoPtCr films deposited on Ru seed layers showed large  $K_{u1}$  values of up to  $1.2 \times 10^7$  erg/cm<sup>3</sup>, but with negligibly small  $K_{u2}$ . The increase in c/a values with the use of adequate seed layer materials led to the appearance of  $K_{u2}$ . However,  $K_{u1}$  decreased as the c/a increased, resulting in a reduction of total anisotropy,  $K_{u1}(=K_{u1}+K_{u2})$ . This correlation between c/a and  $(K_{u1}, K_{u2})$  is qualitatively in good agreement with theoretical predictions [8], [9].

Fig. 2 shows the values of  $K_{u1}$  and  $K_{u2}$  for  $(Co_{90}Cr_{10})$ <sub>75</sub>Pt<sub>25</sub> films as a function of the c/a values. The values of  $K_{u1}$ and  $K_{u2}$  have a greater dependence on the seed layer material used compared to the media with 20at%Pt, and some CoPtCr films show large  $K_{u2}$  of  $3-4 \times 10^6$  erg/cm<sup>3</sup> with  $K_{u1} = \sim 0$ (Cone state of magnetization). It should be noted that the relationship between c/a and  $(K_{u1}, K_{u2})$  is unclear, compared to the CoPtCr films with 20 at%Pt composition.

Grazing incidence XRD analysis using Synchrotron radiation showed that very weak fcc-lattice diffractions could be observed in the CoPtCr films, although no fcc-lattice diffraction lines were observed in XRD patterns measured by a conventional XRD analysis using Cu-K $\alpha$  radiation. Table I shows the ratio of the diffraction intensity of fcc(111) to that of hcp(101) for (Co<sub>90</sub>Cr<sub>10</sub>)<sub>80</sub>Pt<sub>20</sub> films deposited on Ru, Pt and Pd seed layers. The values of the intensity ratio were normalized to that of the film deposited on the Ru seed layer. The  $K_{u1}$  and  $K_{u2}$ 



Fig. 3. Relationship between the values of  $K_{u1}$  and  $K_{u2}$  of CoPtCr films and CoPtCr-SiO<sub>2</sub> media (shaded area).

values of these films are also shown in the table. This result shows that the value of  $K_{u2}/K_{u1}$  increases as the diffraction intensity of the fcc-lattice increases. It is likely that the increase in the diffraction intensity of the fcc-lattice is caused by an increase in the density of stacking-faults in the hcp-lattice. Kubo, *et al.* revealed [10] that the CoPtCr(-SiO<sub>2</sub>) films show a very high stacking-fault density in the Pt content region higher than 20 at%Pt. It is assumed that the appearance of  $K_{u2}$  is related to an increase in the density of stacking-faults in the hcp-lattice in addition to the lattice deformation, especially in the Pt content region higher than 20 at%Pt, which results in the unclear relationship between c/a and  $(K_{u1}, K_{u2})$  shown in Fig. 2.

Fig. 3 shows the relationship between the values of  $K_{u1}$  and  $K_{u2}$  for the (Co<sub>90</sub>Cr<sub>10</sub>) <sub>80</sub>Pt<sub>20</sub> films deposited on various kinds of seed layer materials.  $K_{u1}$  decreases almost linearly as  $K_{u2}$ increases. This almost linear relationship was also observed for  $(Co_{90}Cr_{10})$  <sub>75</sub>Pt<sub>25</sub> films [5]. The addition of SiO<sub>2</sub> reduces the total anisotropy as indicated by the shaded area, but no significant change in the values of  $K_{u2}/K_{u1}$  was observed on the addition of  $SiO_2$  [5], [6]. Theoretical calculations for media designs for 400 Gb/in<sup>2</sup> revealed [5] that the values of  $K_{u1}$  and  $K_{u2}$  are required to be 4.3  $\times 10^6$  erg/cm<sup>3</sup> and 0.9–1.5  $\times 10^6$ erg/cm<sup>3</sup>, respectively (the saturation magnetization,  $M_s$ , is 500-600 emu/cm<sup>3</sup>), to enhance the energy barrier for the remanent state without a notable change in the switching field. The experimental results shown in Fig. 3 indicate that the required values of  $K_{u1}$  and  $K_{u2}$  are achievable by controlling the lattice deformation. The most important point is control of the microstructure to enhance grain isolation whilst simultaneously achieving adequate magnitudes of  $K_{u1}$  and  $K_{u2}$ .

We did some studies of ways to enhance the grain isolation, and Fig. 4 shows the magnetization curve of a prototype CoPtCr-SiO<sub>2</sub> medium. The values of  $K_{u1}, K_{u2}, M_s$ , and the grain size, including the grain boundary thickness,  $D_{\text{grain}}$ , are shown in Table II. The values required for 400 Gb/in <sup>2</sup> [5] are also shown for comparison. The values of  $K_{u1}, K_{u2}$ , and  $D_{\text{grain}}$  satisfy the required values, although  $M_s$  is still too large. The values of remanence coercivity measured at ~10 Oe/s,  $H_r$ , and ~ 10<sup>8</sup> Oe/s,  $H_r^P$ , were 3.9 and 4.5 kOe, respectively. The values of  $H_0$  and  $K_u V_{\text{act}}/kT$  were obtained



Fig. 4. Magnetization loop of the prototype  $K_{u2}$ -medium.

TABLE II MAGNETIC ANISOTROPY FOR THE K $_{u2}$  Media Preliminary Fabricated

	CoPtCr-SiO <sub>2</sub> /Pd	Required values (400 Gbits/inch <sup>2</sup> )
$K_{u1} (x10^6 \text{ erg/cm}^3)$	4.6	4.3
$K_{u2} (x10^6 \text{ erg/cm}^3)$	1.3	0.9-1.5
$K_{u2}/K_{u1}$	0.27	0.2-0.35
$M_s (emu/cm^3)$	700	500-600
D <sub>grain</sub> (nm)	~7	< 8.4



Fig. 5. Recording performance of the prototype  $K_{u2}$ -medium with SUL.

by fitting the values of  $H_r$  and  $H_r^P$  to Sharrock's equation [11], taking account of the influence of  $K_{u2}$  on the Sharrock's equation [12]. ( $V_{\text{act}}$  is the activation volume, k the Boltzmann constant, and T the absolute temperature).  $H_0$  corresponds to the "intrinsic" remanence coercivity obtained by subtracting the effect of the thermal agitation of magnetization. The value of  $H_0$  was ~ 5.0 kOe, which was about 40% of the anisotropy field determined from  $K_{u1}$  term,  $H_{k1}$ , indicating that a possibly further grain isolation is required. However, the medium shows relatively good recording performance as seen in Fig. 5; the value of signal to medium noise ratio crosses the zero line at  $\sim 630$  kFCI, and the recording resolution (the linear recording density where the readout signal becomes half that at low density),  $D_{50}$ , is ~ 405 kFCI. The value of  $K_u V_{act}/kT$  of this medium was 240. The value of  $\Delta E V_{\rm act}/kT (\Delta E$  is the stabilizing energy barrier) in the saturation remanent magnetization

### **IV. CONCLUSION**

The values of  $K_{u1}$  and  $K_{u2}$  of CoPtCr-SiO<sub>2</sub> media are related to the deformation of the hcp–CoPtCr lattice, moreover, a high stacking-fault density is likely to enhance the  $K_{u2}$ values, especially in the high Pt content region. The fabrication of CoPtCr–SiO<sub>2</sub> media having adequate values of  $K_{u1}$  and  $K_{u2}$  was successfully demonstrated, although a more intensive effort is required to confirm advantages of the  $K_{u2}$  term.

#### ACKNOWLEDGMENT

This work was supported in part by the IT-Program (RR2002), Ministry of Education, Culture, Sports, Science and Technology (MEXT).

#### REFERENCES

- H. N. Bertram and V. L. Safonov, "The effect of uniaxial quartic anisotropy on thermal stability of magnetic nanograins," *Appl. Phys. Lett.*, vol. 79, pp. 4402–4404, 2001.
- [2] O. Kitakami, S. Okamoto, N. Kikuchi, and Y. Shimada, "Energy barrier enhanced by higher order magnetic anisotropy," *Jpn. J. Appl. Phys.*, vol. 42, pp. L455–L457, May 2003.
- [3] Q. Peng and H. J. Richter, "Analysis of thermal effects in thin-film media," J. Appl. Phys., vol. 93, pp. 7399–7401, 2003.
- [4] L. Guan, Y. S. Tang, B. Hu, and J. G. Zhu, "Thermal stability enhancement of perpendicular media with high-order uniaxial anisotropy," *IEEE Trans. Magn.*, vol. 40, no. 4, pp. 2579–2581, Jul. 2004.
- [5] T. Shimatsu, H. Sato, T. Oikawa, Y. Inaba, O. Kitakami, S. Okamoto, H. Aoi, H. Muraoka, and Y. Nakamura, "High potential magnetic anisotropy of CoPtCr-SiO<sub>2</sub> perpendicular recording media," *IEEE Trans. Magn.*, vol. 41, no. 2, pp. 566–571, Feb. 2005.
- [6] T. Shimatsu, H. Sato, K. Mitsuzuka, T. Oikawa, Y. Inaba, H. Aoi, H. Muraoka, Y. Nakamura, O. Kitakami, and S. Okamoto, "K<sub>u2</sub> magnetic anisotropy term of CoPtCr-SiO<sub>2</sub> media for high density recording," J. Appl. Phys., vol. 97, no. 10, pp. 10N111–10N111–3, May 2005.
- [7] S. Okamoto, N. Kikuchi, O. Kitakami, T. Miyazaki, Y. Shimada, and K. Fukamichi, "Chemical-order-dependent magnetic anisotropy and exchange stiffness constant of FePt(001) epitaxial films," *Phys. Rev. B*, vol. 66, pp. 244 131–244 139, 2002.
- [8] W. J. Carr Jr., "Theory of ferromagnetic anisotropy," *Phys. Rev.*, vol. 108, pp. 1158–1163, 1957.
- [9] —, "Temperature dependence of ferromagnetic anisotropy," *Phys. Rev.*, vol. 109, pp. 1971–1976, 1958.
- [10] T. Kubo, Y. Kuboki, M. Ohsawa, R. Tanuma, A. Saito, T. Oikawa, H. Uwazumi, and T. Shimatsu, "Crystallographic analysis of CoPtCr-SiO<sub>2</sub> perpendicular recording media with high anisotropy using synchrotron radiation X-ray diffraction," *J. Appl. Phys.*, vol. 97, no. 10, May 2005.
- [11] M. P. Sharrock, "Time dependence of switching fields in magnetic recording media (invited)," J. Appl. Phys., vol. 76, pp. 6413–6418, 1994.
- [12] O. Kitakami, T. Shimatsu, S. Okamoto, Y. Shimada, and H. Aoi, "Scharrock's relation for perpendicular recording media with high-order magnetic anisotropy term," *Jpn. J. Appl. Phys.*, vol. 43, pp. L115–L117, 2004.

Manuscript received February 7, 2005.